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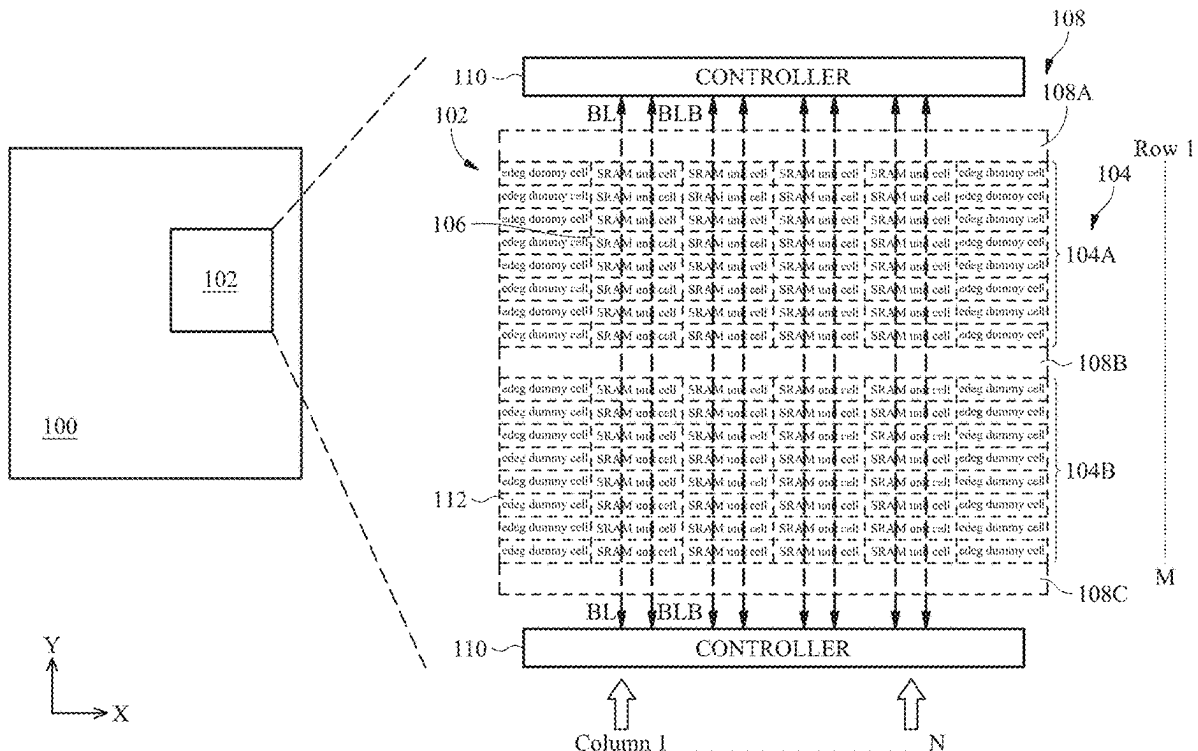
(19) **United States**(12) **Patent Application Publication****Yang et al.**(10) **Pub. No.: US 2025/0261356 A1**(43) **Pub. Date: Aug. 14, 2025**(54) **WELL PICK-UP REGION DESIGN FOR IMPROVING MEMORY MACRO PERFORMANCE****Publication Classification**(51) **Int. Cl.****H10B 10/00** (2023.01)**G06F 30/30** (2020.01)**G11C 11/412** (2006.01)(52) **U.S. Cl.**CPC ..... **H10B 10/00** (2023.02); **G06F 30/30** (2020.01); **G11C 11/412** (2013.01)(71) Applicant: **Taiwan Semiconductor Manufacturing Co., Ltd.**, Hsin-Chu (TW)(72) Inventors: **Chih-Chuan Yang**, Hsinchu (TW);  
**Chang-Ta Yang**, Hsinchu City (TW);  
**Ping-Wei Wang**, Hsin-Chu (TW)(21) Appl. No.: **19/169,160**(22) Filed: **Apr. 3, 2025****Related U.S. Application Data**

(60) Continuation of application No. 18/444,889, filed on Feb. 19, 2024, now Pat. No. 12,274,045, which is a continuation of application No. 17/873,626, filed on Jul. 26, 2022, now Pat. No. 11,910,585, which is a division of application No. 16/657,421, filed on Oct. 18, 2019, now Pat. No. 11,600,623.

(60) Provisional application No. 62/771,455, filed on Nov. 26, 2018.

(57) **ABSTRACT**

Well pick-up (WPU) regions are disclosed herein for improving performance of semiconductor devices. An exemplary semiconductor device includes a circuit region, a WPU region, a first well oriented lengthwise along a first direction in the circuit region and extending into the WPU region, and a second well oriented lengthwise along the first direction in the circuit region and extending into the WPU region. The first well having a first conductivity type, and the second well having a second conductivity type different from the first conductivity type. In the circuit region, the first well interfaces the second well to form a first well boundary extending along the first direction. Measured along a second direction perpendicular to the first direction, the first well has a larger width in the WPU region than in the circuit region.



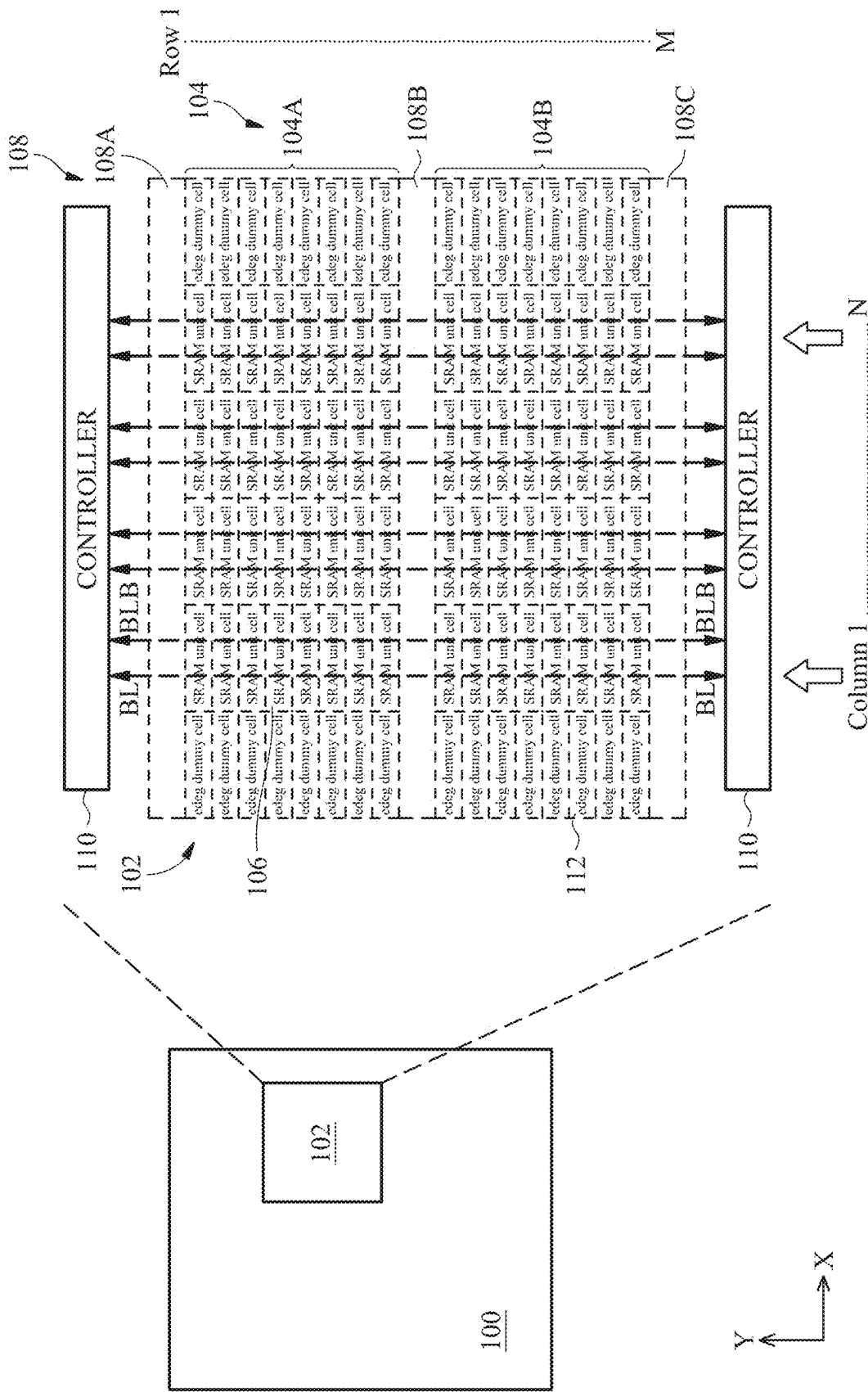


FIG. 1

200

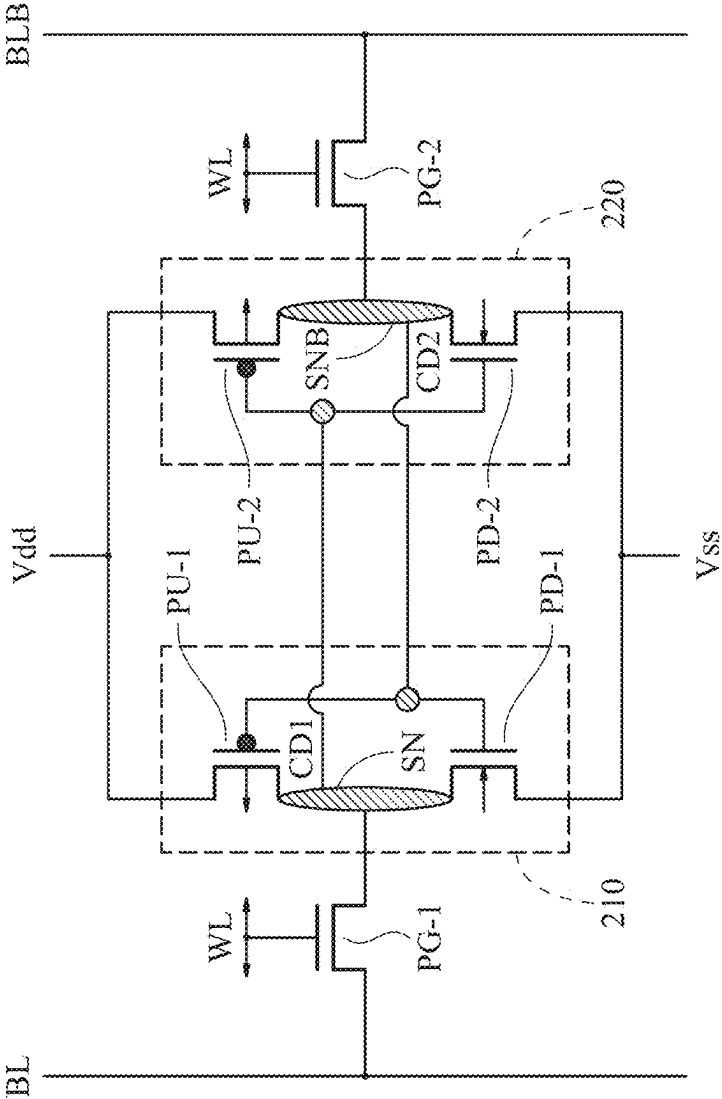


FIG. 2

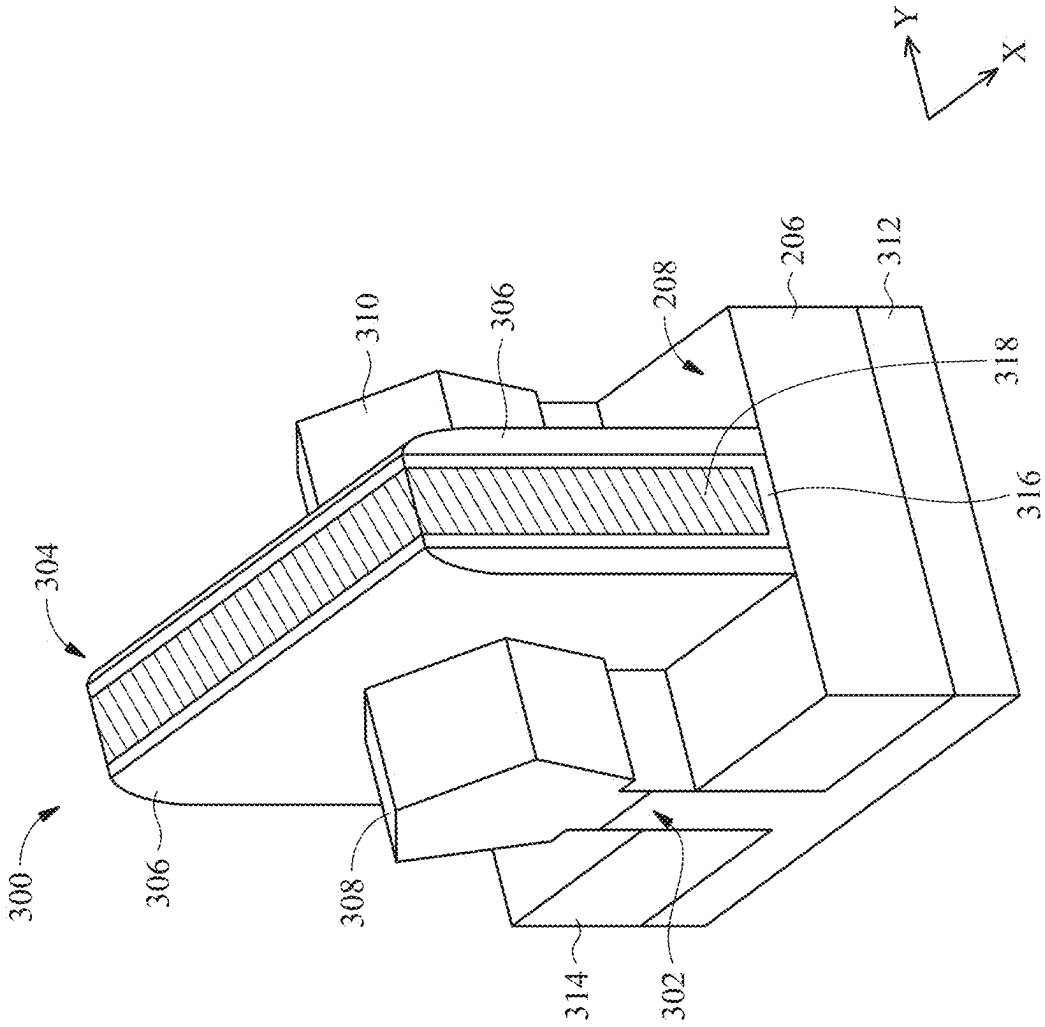


FIG. 3

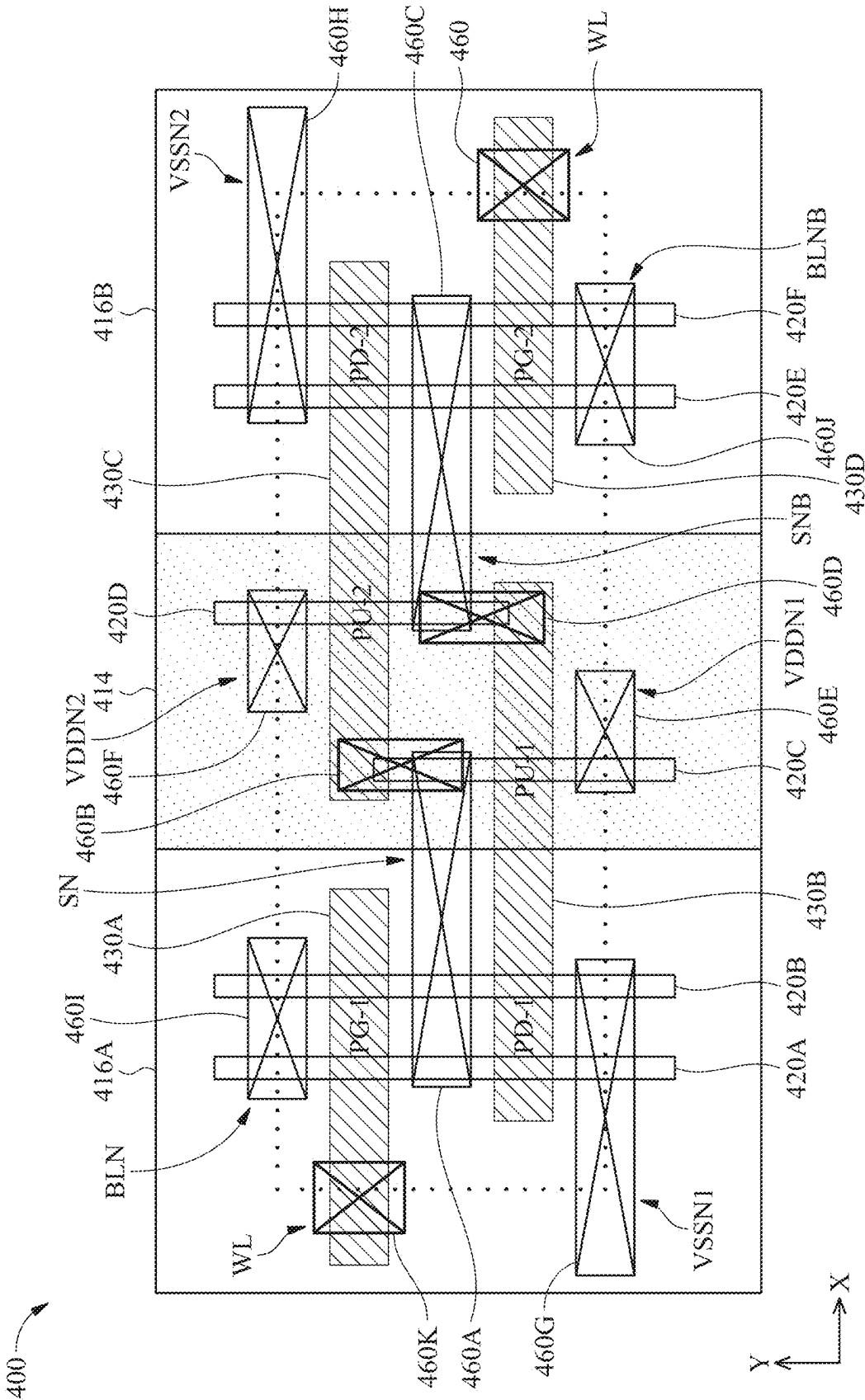


FIG. 4

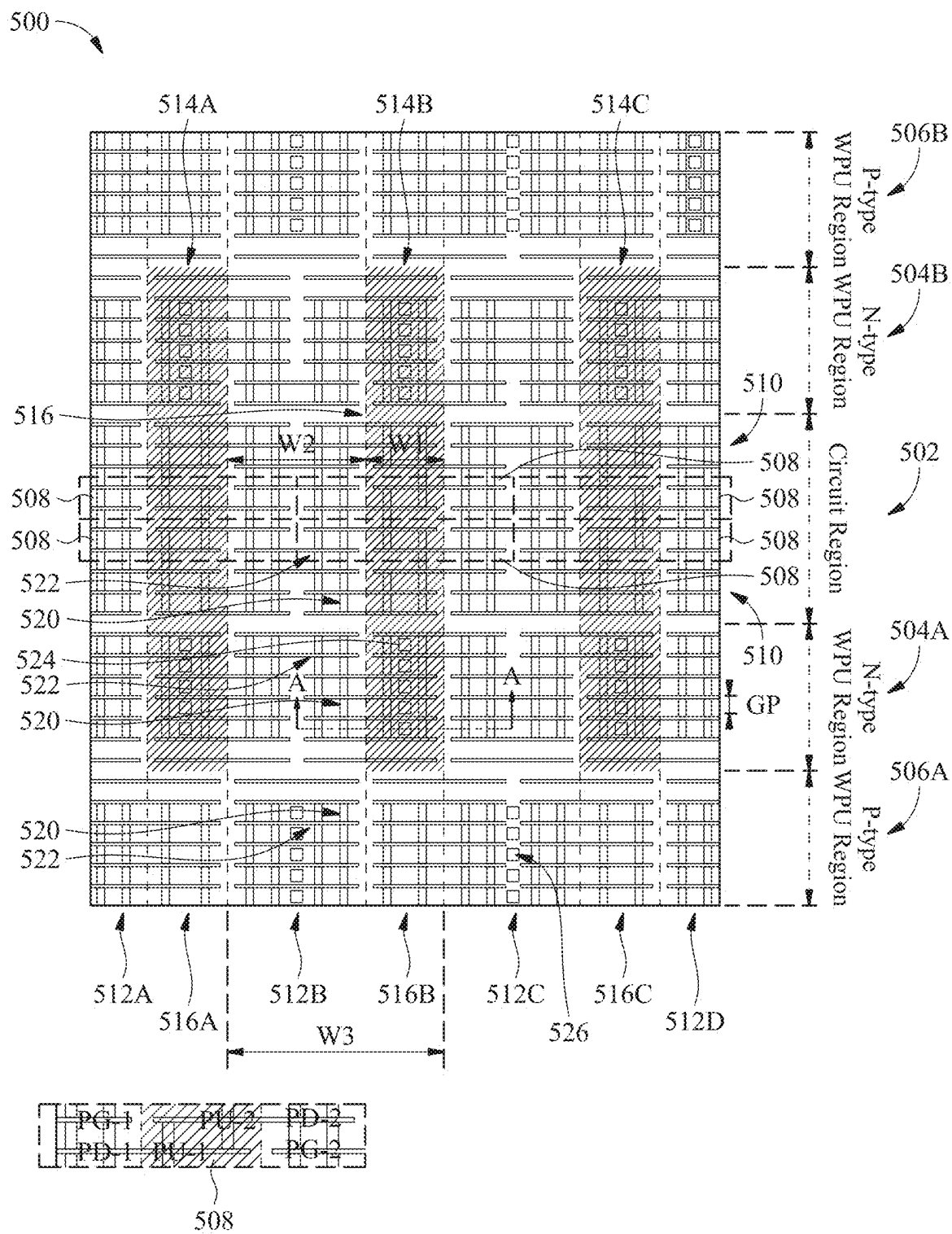


FIG. 5

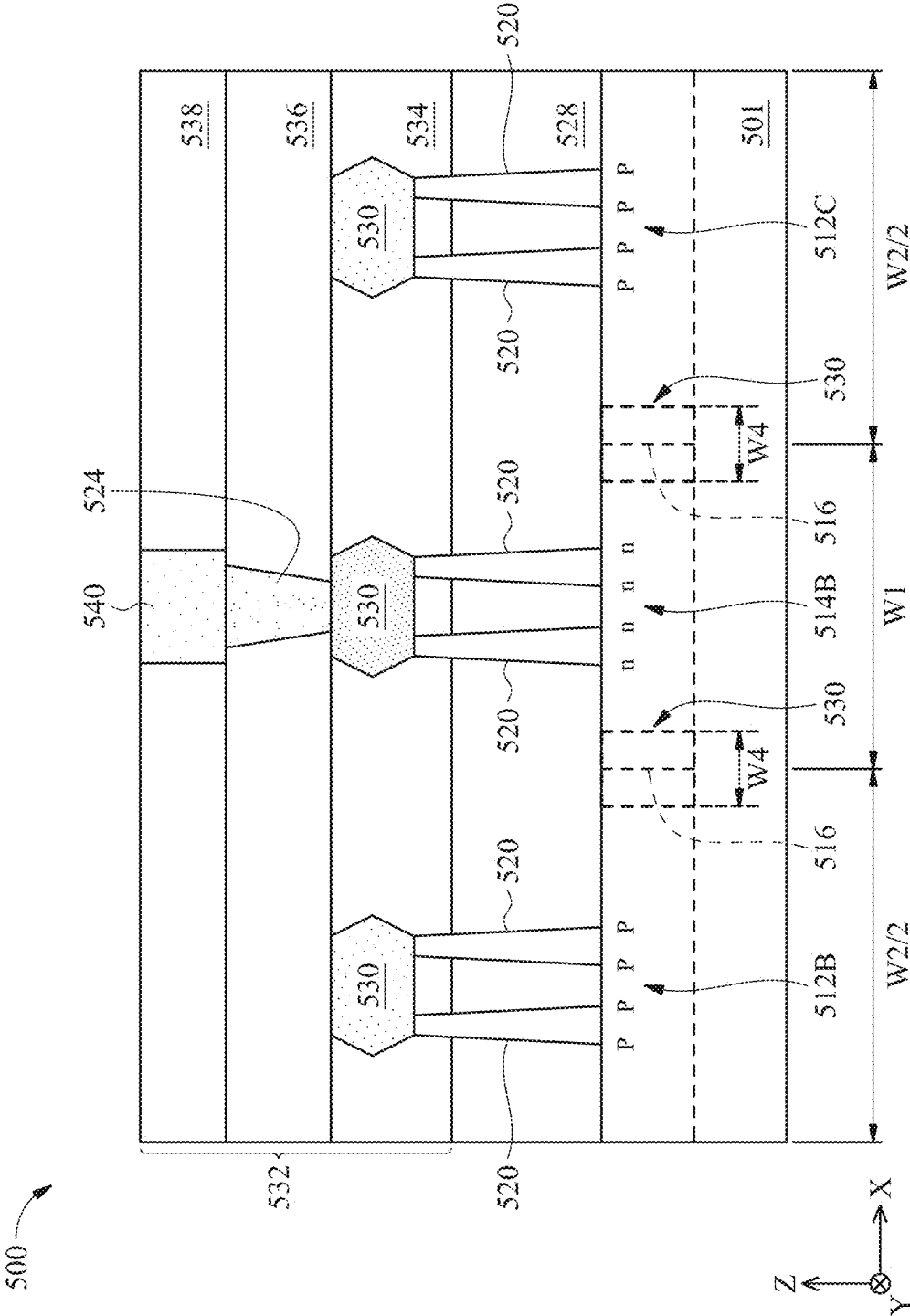
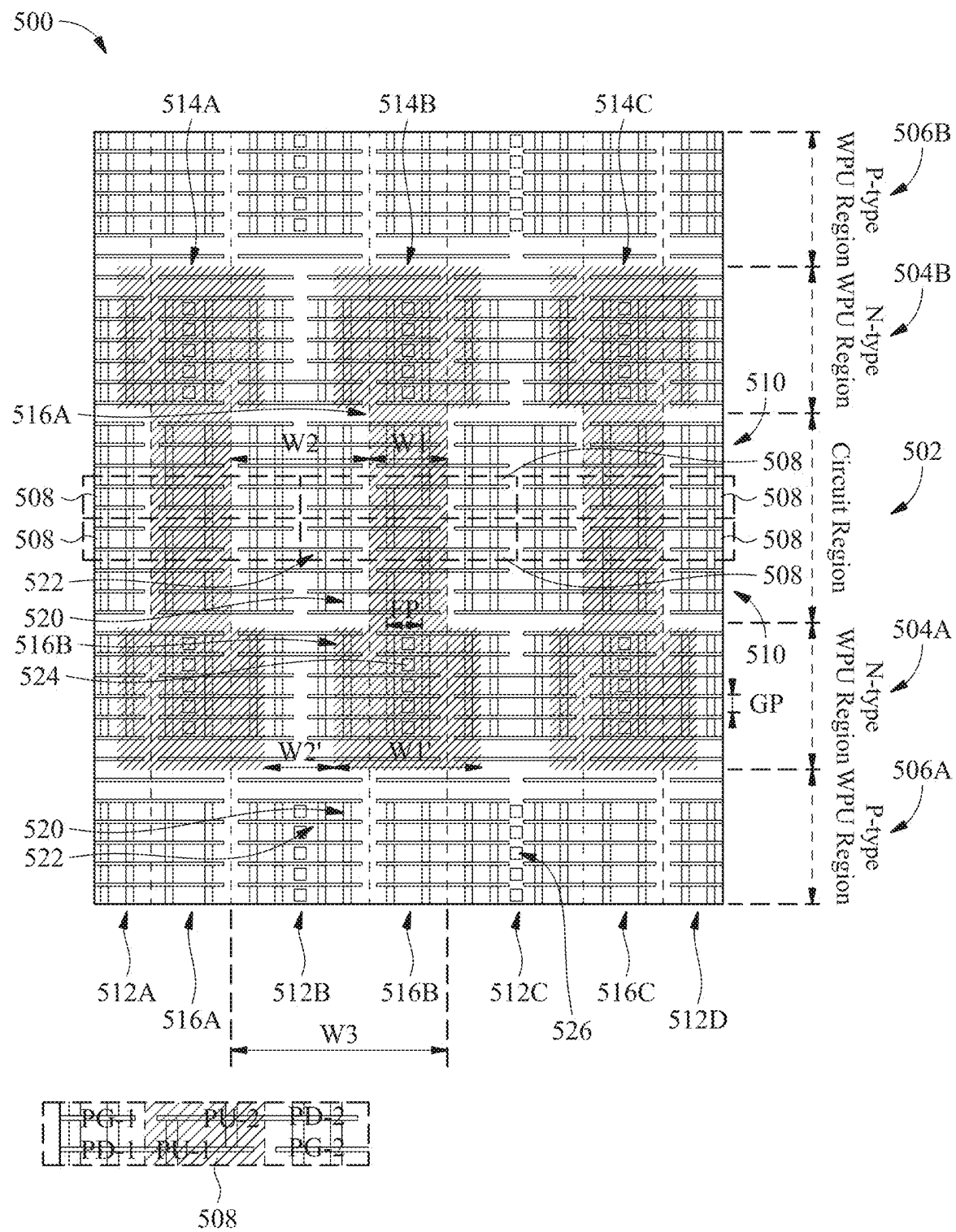
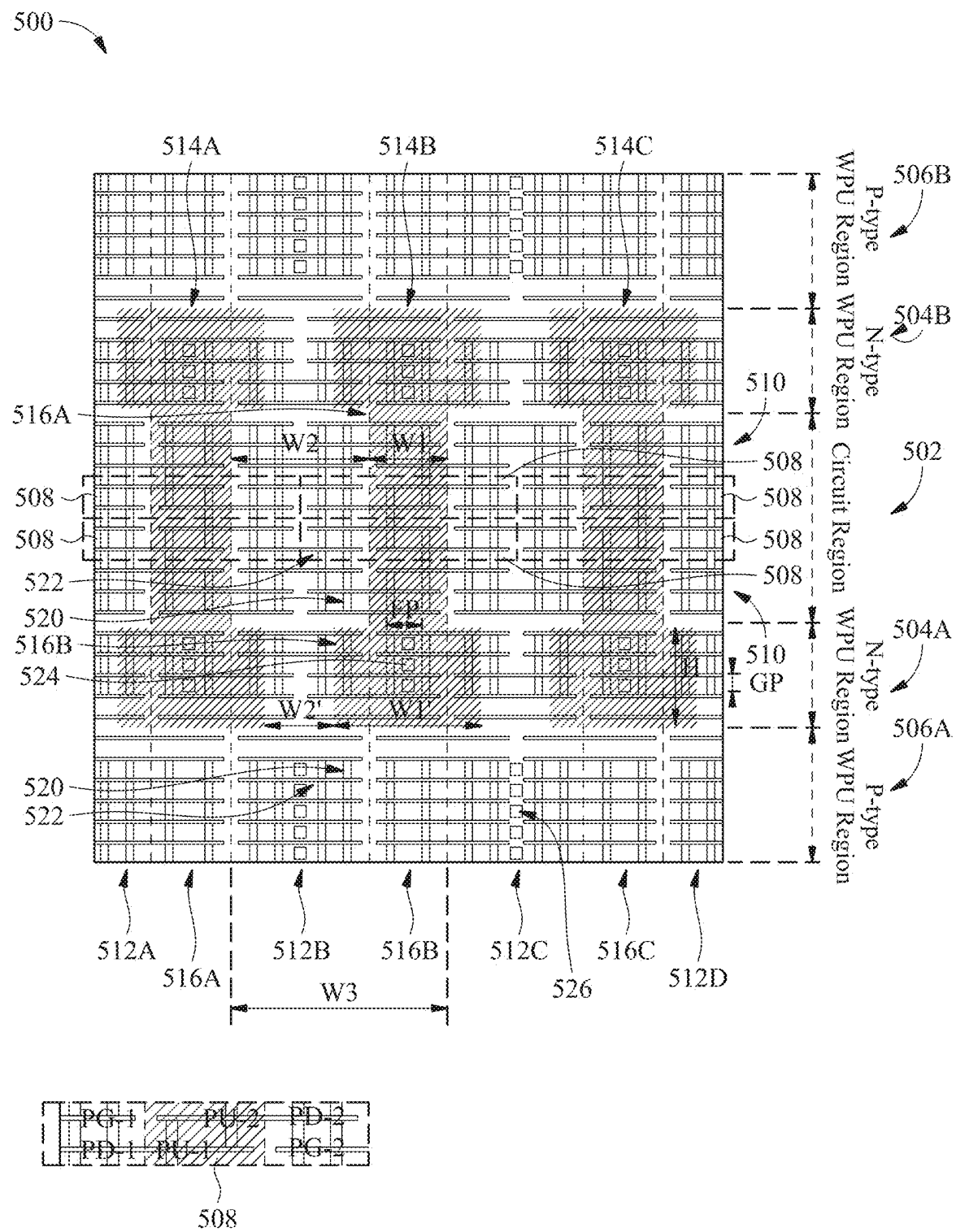


FIG. 6







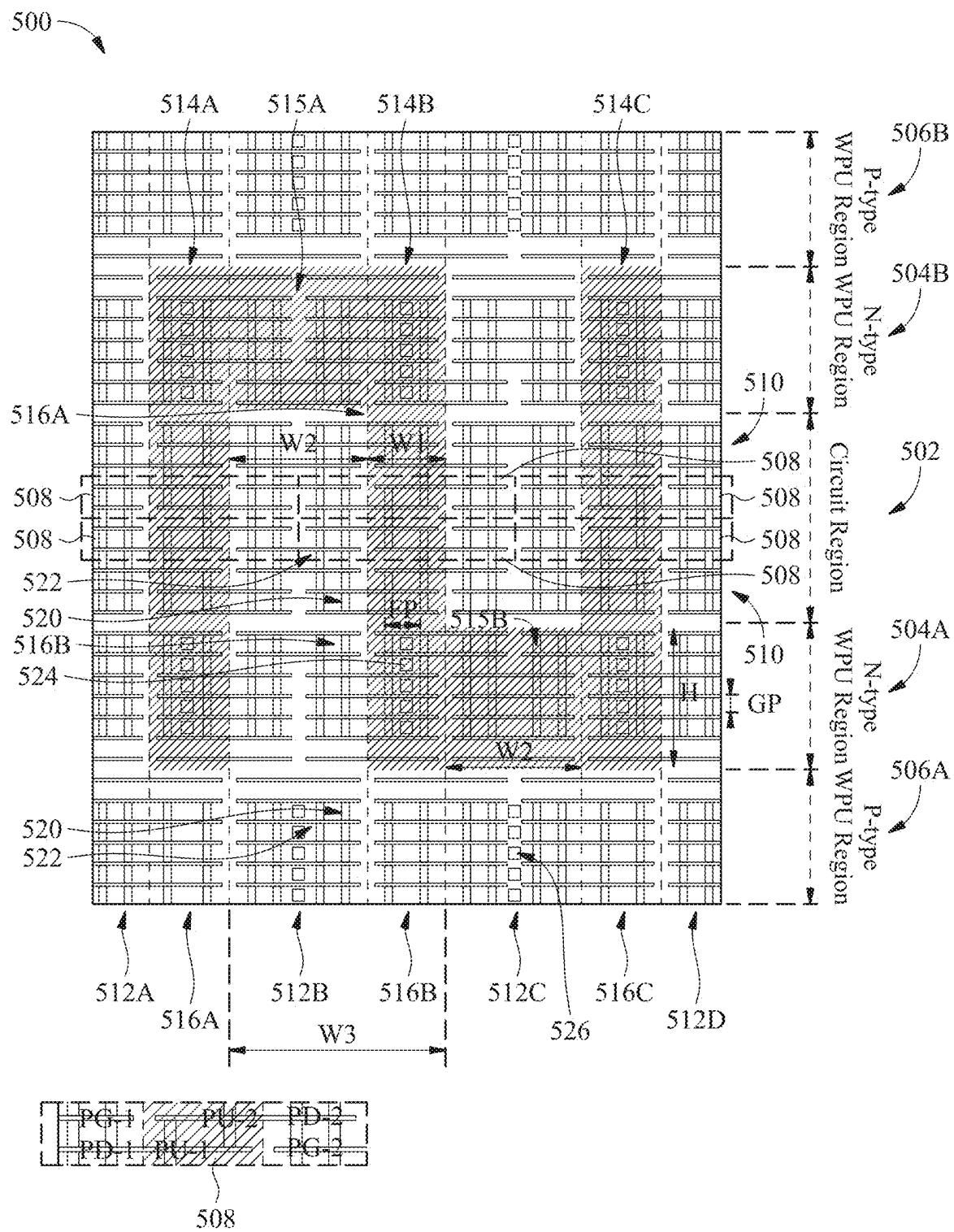


FIG. 9

## WELL PICK-UP REGION DESIGN FOR IMPROVING MEMORY MACRO PERFORMANCE

### PRIORITY

[0001] This is a continuation application of U.S. patent application Ser. No. 18/444,889 filed Feb. 19, 2024, which is a continuation application of U.S. patent application Ser. No. 17/873,626 filed Jul. 26, 2022, now issued U.S. Pat. No. 11,910,585, which is a divisional application of U.S. patent application Ser. No. 16/657,421 filed Oct. 18, 2019, now issued U.S. Pat. No. 11,600,623, which claims benefit of U.S. Provisional Patent Application Ser. No. 62/771,455, filed Nov. 26, 2018, the entire disclosures of which are incorporated herein by reference.

### BACKGROUND

[0002] The semiconductor integrated circuit (IC) industry has experienced exponential growth. Technological advances in IC materials and design have produced generations of ICs where each generation has smaller and more complex circuits than the previous generation. In the course of IC evolution, functional density (i.e., the number of interconnected devices per chip area) has generally increased while geometry size (i.e., the smallest component (or line) that can be created using a fabrication process) has decreased. This scaling down process generally provides benefits by increasing production efficiency and lowering associated costs. Such scaling down has also increased the complexity of processing and manufacturing ICs.

[0003] For example, in memory devices, such as static random-access memory (SRAM), leakage issue becomes more severe in advanced process nodes. SRAM generally refers to a memory or a storage that can retain stored data only when power is applied. Since SRAM cell performance is largely layout dependent (for example, it has been observed that an inner SRAM cell of an SRAM macro will perform differently than an edge SRAM cell of the SRAM macro), well pick-up regions (or areas) have been implemented to stabilize well potential, facilitating uniform charge distribution throughout an SRAM macro, and thus uniform performance among SRAM cells of the SRAM array. However, as circuit geometry shrinks, leakage between adjacent n-type wells (or n-wells) and p-type wells (or p-wells) becomes more severe due to dopant diffusion. This leads to higher n-well and p-well resistance in well pick-up regions and higher pick-up resistance, which deteriorates latch-up performance. Accordingly, although existing well pick-up region designs for SRAM macros have been generally adequate for their intended purposes, they have not been entirely satisfactory in all respects.

### BRIEF DESCRIPTION OF THE DRAWINGS

[0004] The present disclosure is best understood from the following detailed description when read with the accompanying figures. It is emphasized that, in accordance with the standard practice in the industry, various features are not drawn to scale and are used for illustration purposes only. In fact, the dimensions of the various features may be arbitrarily increased or reduced for clarity of discussion.

[0005] FIG. 1 is a simplified block diagram of an integrated circuit (IC) with an embedded memory macro, according to various aspects of the present disclosure.

[0006] FIG. 2 is a circuit diagram of a single-port SRAM cell, which can be implemented in a memory cell of a memory macro, according to various aspects of the present disclosure.

[0007] FIG. 3 is a perspective view of a fin field-effect transistor (FinFET) in accordance with some embodiments.

[0008] FIG. 4 is a plan view of a single-port SRAM cell, which can be implemented in a memory cell of a memory macro, according to various aspects of the present disclosure.

[0009] FIGS. 5, 7, 8, and 9 are fragmentary plan views of a portion of a memory array according to various aspects of the present disclosure.

[0010] FIG. 6 is a fragmentary diagrammatic view of a portion of a memory array according to various aspects of the present disclosure.

### DETAILED DESCRIPTION

[0011] The following disclosure provides many different embodiments, or examples, for implementing different features of the invention. Specific examples of components and arrangements are described below to simplify the present disclosure. These are, of course, merely examples and are not intended to be limiting. For example, the formation of a first feature over or on a second feature in the description that follows may include embodiments in which the first and second features are formed in direct contact, and may also include embodiments in which additional features may be formed between the first and second features, such that the first and second features may not be in direct contact.

[0012] In addition, the present disclosure may repeat reference numerals and/or letters in the various examples. This repetition is for the purpose of simplicity and clarity and does not in itself dictate a relationship between the various embodiments and/or configurations discussed. Moreover, the formation of a feature on, connected to, and/or coupled to another feature in the present disclosure that follows may include embodiments in which the features are formed in direct contact, and may also include embodiments in which additional features may be formed interposing the features, such that the features may not be in direct contact. In addition, spatially relative terms, for example, “lower,” “upper,” “horizontal,” “vertical,” “above,” “over,” “below,” “beneath,” “up,” “down,” “top,” “bottom,” etc. as well as derivatives thereof (e.g., “horizontally,” “downwardly,” “upwardly,” etc.) are used for ease of the present disclosure of one features relationship to another feature. The spatially relative terms are intended to cover different orientations of the device including the features. Still further, when a number or a range of numbers is described with “about,” “approximate,” and the like, the term is intended to encompass numbers that are within  $\pm 10\%$  of the number described, unless otherwise specified. For example, the term “about 5 nm” encompasses the dimension range from 4.5 nm to 5.5 nm.

[0013] The present disclosure is generally related to semiconductor devices, and more particularly to the placement of n-wells and p-wells in a memory macro's well pick-up (WPU) regions. The WPU regions provide well pick-up structures (or tap structures), such as well tap contact plugs, in the memory macro. The well pick-up structures provide access to the n-wells and p-wells underlying the transistors in the memory macro. For example, tester pins may contact the well pick-up structures to provide voltages to the wells

during manufacturing testing. For example, package pins or pads may be connected to the well pick-up structures in a final IC having the memory macro. The n-wells and p-wells (which are doped with opposite dopants) are arranged alternately in a memory macro (i.e., an n-well is next to a p-well which is next to another n-well) and have separate well pick-up structures. Opposite dopants diffuse through well boundaries between adjacent n-wells and p-wells and create diffusion areas along well boundaries. The diffusion areas reduce effective widths of n-wells and p-wells and lead to higher well pick-up resistance. As the widths of n-wells and p-wells continue to scale down with modern technology nodes, the negative impact of diffusion areas on well pick-up resistance becomes more threatening to circuit functions. For example, leakage current between the oppositely doped wells becomes a concern with higher well pick-up resistance because it may trigger latch-up more easily in the circuit. An object of the present disclosure is to mitigate this problem by arranging the placement of n-wells and p-wells in a memory macro's WPU regions to reduce well pick-up resistance.

**[0014]** FIG. 1 shows a semiconductor device **100** with a memory macro **102**. The semiconductor device **100** can be, e.g., a microprocessor, an application specific integrated circuit (ASIC), a field programmable gate array (FPGA), or a digital signal processor (DSP). Further, semiconductor device **100** may be a portion of an IC chip, an SoC, or portion thereof, that includes various passive and active microelectronic devices such as resistors, capacitors, inductors, diodes, PFETs, NFETs, MOSFETs, CMOS transistors, BJTs, LDMOS transistors, high voltage transistors, high frequency transistors, other suitable components, or combinations thereof. The exact functionality of semiconductor device **100** is not a limitation to the provided subject matter. In the illustrated embodiment, memory macro **102** is a static random access memory (SRAM) macro, such as a single-port SRAM macro, a dual-port SRAM macro, or other types of SRAM macro. However, the present disclosure contemplates embodiments, where memory macro **102** is another type of memory, such as a dynamic random access memory (DRAM), a non-volatile random access memory (NVRAM), a flash memory, or other suitable memory. FIG. 1 has been simplified for the sake of clarity to better understand the inventive concepts of the present disclosure. Additional features can be added in memory macro **102**, and some of the features described below can be replaced, modified, or eliminated in other embodiments of memory macro **102**.

**[0015]** Memory macro **102** includes one or more circuit regions **104**, such as circuit regions **104A** and **104B** in the illustrated embodiment. Circuit regions **104** contain all the memory cells **106** of memory macro **102**. Circuit regions **104** are also referred to as memory cell regions **104**. Memory cells **106** are generally implemented in forms of arrays in circuit regions **104**. Each memory cell **106**, such as an SRAM memory cell, is configured to store data. Memory cell **106** may be implemented with various PMOS and NMOS transistors such as planar transistors, FinFET, gate-all-around (GAA) nanosheet transistors, GAA nanowire transistors, or other types of transistors. In the illustrated embodiment, memory cells **106** include various p-type FinFETs and n-type FinFETs.

**[0016]** Memory macro **102** also includes one or more strap regions **108**, such as strap regions **108A**, **108B**, and **108C** oriented lengthwise along an x-direction in the illustrated embodiment. Strap regions **108A** and **108C** are located at the

edge of memory macro **102** and strap region **108B** is located between circuit regions **104A** and **104B**. Each of strap regions **108** does not contain memory cells and is used for implementing well pick-up structures. A well pick-up structure is generally configured to electrically couple a voltage to an n-well of memory cells **106** or a p-well of memory cells **106**. Strap regions **108** are also referred to as well pick-up (WPU) regions **108**.

**[0017]** Further, memory macro **102** may include various contact features (or contacts), vias, and metal lines for connecting the source, drain, and gate electrodes (or terminals) of the transistors to form an integrated circuit.

**[0018]** Still referring to FIG. 1, memory cells **106** are arranged in column **1** to column **N** each extending along a first direction (here, in a y-direction) and row **1** to row **M** each extending along a second direction (here, in an x-direction), where **N** and **M** are positive integers. Column **1** to column **N** each include a bit line pair extending along the first direction, such as a bit line (BL) and a bit line bar (BLB) (also referred to as a complementary bit line), that facilitate reading data from and/or writing data to respective memory cells **106** in true form and complementary form on a column-by-column basis. Row **1** to row **M** each includes a word line (WL) (not shown) that facilitates access to respective memory cells **106** on a row-by-row basis. Each memory cell **106** is electrically connected to a respective BL, a respective BLB, and a respective WL, which are electrically connected to a controller **110**. Controller **110** is configured to generate one or more signals to select at least one WL and at least one bit line pair (here, BL and BLB) to access at least one of memory cells **106** for read operations and/or write operations. Controller **110** includes any circuitry suitable to facilitate read/write operations from/to memory cells **106**, including but not limited to, a column decoder circuit, a row decoder circuit, a column selection circuit, a row selection circuit, a read/write circuit (for example, configured to read data from and/or write data to memory cells **106** corresponding to a selected bit line pair (in other words, a selected column)), other suitable circuit, or combinations thereof. In some implementations, controller **110** includes at least one sense amplifier (not shown) configured to detect and/or amplify a voltage differential of a selected bit line pair. In some implementations, the sense amplifier is configured to latch or otherwise store data values of the voltage differential.

**[0019]** A perimeter of memory macro **102** is configured with dummy cells, such as edge dummy cells **112**, to ensure uniformity in performance of memory cells **106**. Dummy cells are configured physically and/or structurally similar to memory cells **106**, but do not store data. For example, dummy cells can include p-type wells, n-type wells, fin structures (including one or more fins), gate structures, source/drain features, and/or contact features. In the illustrated embodiment, row **1** to row **M** each begins with an edge dummy cell **112** and ends with an edge dummy cell **112**, such that row **1** to row **M** of memory cells **106** are disposed between two edge dummy cells **112**.

**[0020]** FIG. 2 is a circuit diagram of a single-port SRAM cell **200**, which can be implemented in a memory cell of a SRAM array, according to various aspects of the present disclosure. In some implementations, SRAM cell **200** is implemented in one or more memory cells **106** of memory macro **102** (FIG. 1). FIG. 2 has been simplified for the sake of clarity to better understand the inventive concepts of the

present disclosure. Additional features can be added in single-port SRAM cell **200**, and some of the features described below can be replaced, modified, or eliminated in other embodiments of single-port SRAM cell **200**.

**[0021]** Single-port SRAM cell **200** includes six transistors: a pass-gate transistor PG-1, a pass-gate transistor PG-2, a pull-up transistor PU-1, a pull-up transistor PU-2, a pull-down transistor PD-1, and a pull-down transistor PD-2. Single-port SRAM cell **200** is thus alternatively referred to as a 6T SRAM cell. In operation, pass-gate transistor PG-1 and pass-gate transistor PG-2 provide access to a storage portion of SRAM cell **200**, which includes a cross-coupled pair of inverters, an inverter **210** and an inverter **220**. Inverter **210** includes pull-up transistor PU-1 and pull-down transistor PD-1, and inverter **220** includes pull-up transistor PU-2 and pull-down transistor PD-2. In some implementations, pull-up transistors PU-1, PU-2 are configured as p-type FinFETs, and pull-down transistors PD-1, PD-2 are configured as n-type FinFETs. For example, pull-up transistors PU-1, PU-2 each include a gate structure disposed over a channel region of an n-type fin structure (including one or more n-type fins), such that the gate structure interposes p-type source/drain regions of the n-type fin structure (for example, p-type epitaxial source/drain features), where the gate structure and the n-type fin structure are disposed over an n-type well region; and pull-down transistors PD-1, PD-2 each includes a gate structure disposed over a channel region of a p-type fin structure (including one or more p-type fins), such that the gate structure interposes n-type source/drain regions of the p-type fin structure (for example, n-type epitaxial source/drain features), where the gate structure and the p-type fin structure are disposed over a p-type well region. In some implementations, pass-gate transistors PG-1, PG-2 are also configured as n-type FinFETs. For example, pass-gate transistors PG-1, PG-2 each include a gate structure disposed over a channel region of a p-type fin structure (including one or more p-type fins), such that the gate structure interposes n-type source/drain regions of the p-type fin structure (for example, n-type epitaxial source/drain features), where the gate structure and the p-type fin structure are disposed over a p-type well region.

**[0022]** A gate of pull-up transistor PU-1 interposes a source (electrically coupled with a power supply voltage (VDD)) and a first common drain (CD1), and a gate of pull-down transistor PD-1 interposes a source (electrically coupled with a power supply voltage (Vss)) and the first common drain. A gate of pull-up transistor PU-2 interposes a source (electrically coupled with power supply voltage (VDD)) and a second common drain (CD2), and a gate of pull-down transistor PD-2 interposes a source (electrically coupled with power supply voltage (Vss)) and the second common drain. In some implementations, the first common drain (CD1) is a storage node (SN) that stores data in true form, and the second common drain (CD2) is a storage node (SNB) that stores data in complementary form. The gate of pull-up transistor PU-1 and the gate of pull-down transistor PD-1 are coupled with the second common drain, and the gate of pull-up transistor PU-2 and the gate of pull-down transistor PD-2 are coupled with the first common drain. A gate of pass-gate transistor PG-1 interposes a source (electrically coupled with a bit line BL) and a drain, which is electrically coupled with the first common drain. A gate of pass-gate transistor PG-2 interposes a source (electrically

coupled with a complementary bit line BLB) and a drain, which is electrically coupled with the second common drain (CD2). The gates of pass-gate transistors PG-1, PG-2 are electrically coupled with a word line WL. In some implementations, pass-gate transistors PG-1, PG-2 provide access to storage nodes SN, SNB during read operations and/or write operations. For example, pass-gate transistors PG-1, PG-2 couple storage nodes SN, SNB respectively to bit lines BL, BLB in response to voltage applied to the gates of pass-gate transistors PG-1, PG-2 by WLs.

**[0023]** FIG. 3 illustrates a perspective view of a fin field effect transistor (FinFET) **300**, which may serve as any of the transistors in single-port SRAM cell **200** (FIG. 2), including pull-up transistor PU-1, pull-up transistor PU-2, pull-down transistor PD-1, pull-down transistor PD-2, pass-gate transistor PG-1, and pass-gate transistor PG-2. In some embodiments, FinFET **300** includes a semiconductor fin **302**, a gate structure **304**, spacers **306**, a drain region **308**, and a source region **310**. Semiconductor fin **302** extends above a semiconductor substrate **312**. In some embodiments, semiconductor substrate **312** and semiconductor fin **302** are made of the same material. For example, the substrate is a silicon substrate. In some instances, the substrate includes a suitable elemental semiconductor, such as germanium or diamond; a suitable compound semiconductor, such as silicon carbide, gallium nitride, gallium arsenide, or indium phosphide; or a suitable alloy semiconductor, such as silicon germanium, silicon tin, aluminum gallium arsenide, or gallium arsenide phosphide. In some embodiments, the substrate is a silicon on insulator (SOI) layer substrate or a silicon on sapphire (SOS) substrate. In some embodiments, semiconductor substrate **312** and semiconductor fin **302** are made of different materials.

**[0024]** Semiconductor fin **302** may be patterned by any suitable method. For example, semiconductor fin **302** may be patterned using one or more photolithography processes, including double-patterning or multi-patterning processes. Generally, double-patterning or multi-patterning processes combine photolithography and self-aligned processes, allowing patterns to be created that have, for example, pitches smaller than what is otherwise obtainable using a single, direct photolithography process. For example, in one embodiment, a sacrificial layer is formed over a substrate and patterned using a photolithography process. Spacers are formed alongside the patterned sacrificial layer using a self-aligned process. The sacrificial layer is then removed, and the remaining spacers, or mandrels, may then be used to pattern semiconductor fin **302**.

**[0025]** In some embodiments, semiconductor fin **302** of FinFET **300** may be surrounded by isolating features **314** formed on opposite sides of semiconductor fin **302**. Isolating features **314** may electrically isolate an active region (not shown) of FinFET **300** from other active regions. In some embodiments, isolating features **314** are shallow trench isolation (STI), field oxide (FOX), or another suitable electrically insulating structure. For example, semiconductor fin **302** represents semiconductor fins **520A**, **520B**, **520C**, **520D**, **520E**, and **520F** in a layout of a SRAM cell **400** shown in FIG. 4.

**[0026]** Still referring to FIG. 3, in some embodiments, gate structure **304**, which includes a gate dielectric **316** and a gate electrode **318** formed over gate dielectric **316**, is positioned over sidewalls and a top surface of semiconductor fin **302**. Therefore, a portion of semiconductor fin **302**

overlaps gate structure **304** may serve as a channel region of FinFET **300**. In some embodiments, gate dielectric **316** is a high dielectric constant (high-k) dielectric material. A high-k dielectric material has a dielectric constant (k) higher than that of silicon dioxide. Examples of high-k dielectric materials include hafnium oxide, zirconium oxide, aluminum oxide, silicon oxynitride, hafnium dioxide-alumina alloy, hafnium silicon oxide, hafnium silicon oxynitride, hafnium tantalum oxide, hafnium titanium oxide, hafnium zirconium oxide, another suitable high-k material, or a combination thereof. In some embodiments, the gate electrode **318** is made of a conductive material, such as aluminum (Al), copper (Cu), tungsten (W), titanium (Ti), tantalum (Ta), or another applicable material.

[0027] In some embodiments, spacers **306** of FinFET **300** are positioned over sidewalls and a top surface of semiconductor fin **302**. In addition, spacers **306** may be formed on opposite sides of gate structure **304**. In some embodiments, spacers **306** are made of silicon nitride, silicon oxynitride, silicon carbide, another suitable material, or a combination thereof.

[0028] In some embodiments, portions of semiconductor fin **302** that are not covered by gate structure **304** and spacers **306** serve as a drain region **308** and a source region **310**. In some embodiments, drain region **308** and source region **310** of p-type FinFETs, for example, pull-up transistor PU-1 and pull-up transistor PU-2 are formed by implanting the portions of semiconductor fin **302** that are not covered by gate structure **304** and spacers **306** with a p-type impurity such as boron, indium, or the like. In some embodiments, drain region **308** and source region **310** of n-type FinFETs, for example, pass-gate transistor PG-1, pass-gate transistor PG-2, pull-down transistor PD-1, and pull-down transistor PD-2 are formed by implanting the portions of semiconductor fin **302** that are not covered by gate structure **304** and spacers **306** with an n-type impurity such as phosphorous, arsenic, antimony, or the like.

[0029] In some embodiments, drain region **308** and source region **310** are formed by etching portions of semiconductor fin **302** that are not covered by gate structure **304** and spacers **306** to form recesses, and growing epitaxial regions in the recesses. The epitaxial regions may be formed of Si, Ge, SiP, SiC, SiPC, SiGe, SiAs, InAs, InGaAs, InSb, GaAs, GaSb, InAlP, InP, C, or a combination thereof. Accordingly, drain region **308** and source region **310** may be formed of silicon germanium (SiGe) in some exemplary embodiments, while the remaining semiconductor fin **302** may be formed of silicon. In some embodiments, p-type impurities are in-situ doped in drain region **308** and source region **310** during the epitaxial growth of drain region **308** and source region **310** of p-type FinFET **300**, for example, pull-up transistor PU-1 and pull-up transistor PU-2 in FIG. 2. In addition, n-type impurities are in-situ doped in drain region **308** and source region **310** during the epitaxial growth of drain region **308** and source region **310** of n-type FinFET **300**, for example, pass-gate transistor PG-1, pass-gate transistor PG-2, pull-down transistor PD-1, and pull-down transistor PD-2 in FIG. 2.

[0030] In some other embodiments, pass-gate transistors PG-1 and PG-2, pull-up transistors PU-1 and PU-2, and pull-down transistors PD-1 and PD-2 of SRAM cell **200** in FIG. 2 are planar MOS devices.

[0031] FIG. 4 is a layout of a single-port SRAM cell **400**, which can be implemented in a memory cell of a SRAM

array, according to various aspects of the present disclosure. In some implementations, SRAM cell **400** is implemented in one or more memory cells **106** of memory macro **102** (FIG. 1), or as single-port SRAM cell **200** (FIG. 2). FIG. 4 has been simplified for the sake of clarity to better understand the inventive concepts of the present disclosure. Additional features can be added in single-port SRAM cell **400**, and some of the features described below can be replaced, modified, or eliminated in other embodiments of single-port SRAM cell **400**.

[0032] In FIG. 4, single-port SRAM cell **400** includes six transistors: a pass-gate transistor PG-1, a pass-gate transistor PG-2, a pull-up transistor PU-1, a pull-up transistor PU-2, a pull-down transistor PD-1, and a pull-down transistor PD-2. Single-port SRAM cell **400** is thus alternatively referred to as a 6T SRAM cell. Single-port SRAM cell **400** includes an n-well **414** disposed between a p-well **416A** and a p-well **416B**. Pull-up transistors PU-1, PU-2 are disposed over n-well **414**; pull-down transistor PD-1 and pass-gate transistor PG-1 are disposed over p-well **416A**; and pull-down transistor PD-2 and pass-gate transistor PG-2 are disposed over p-well **416B**. In some implementations, pull-up transistors PU-1, PU-2 are configured as p-type FinFETs, and pull-down transistors PD-1, PD-2 and pass-gate transistors PG-1, PG-2 are configured as n-type FinFETs. In some embodiments, each transistor may be in a form similar to FinFET **300** (FIG. 3). In the illustrated embodiment, pull-down transistor PD-1 and pass-gate transistor PG-1 are multi-fin FinFETs (including, for example, a fin **420A** and a fin **420B**), pull-up transistor PU-1 is a single fin FinFET (including, for example, a fin **420C**), pull-up transistor PU-2 is a single fin FinFET (including, for example, a fin **420D**), and pull-down transistor PD-2 and pass-gate transistor PG-2 are multi-fin FinFETs (including, for example, a fin **420E** and a fin **420F**). Fin **420A**, fin **420B**, fin **420E**, and fin **420F** are p-type doped fins, and fin **420C** and fin **420D** are n-type doped fins. A gate structure **430A** is disposed over fins **420A**, **420B**; a gate structure **430B** is disposed over fins **420A**-**420D**; a gate structure **430C** is disposed over fins **420C**-**420F**; and a gate structure **430D** is disposed over fins **420E**, **420F**. A gate of pass-gate transistor PG-1 is formed from gate structure **430A**, a gate of pull-down transistor PD-1 is formed from gate structure **430B**, a gate of pull-up transistor PU-1 is formed from gate structure **430B**, a gate of pull-up transistor PU-2 is formed from gate structure **430C**, a gate of pull-down transistor PD-2 is formed from gate structure **430C**, and a gate of pass-gate transistor PG-2 is formed from gate structure **430D**.

[0033] A device-level contact **460A** electrically connects a drain region of pull-down transistor PD-1 (formed by fins **420A**, **420B** (which can include n-type epitaxial source/drain features)) and a drain region of pull-up transistor PU-1 (formed by fin **420C** (which can include p-type epitaxial source/drain features)), such that a common drain of pull-down transistor PD-1 and pull-up transistor PU-1 form a storage node SN. A device-level contact **460B** electrically connects a gate of pull-up transistor PU-2 (formed by gate structure **430C**) and a gate of pull-down transistor PD-2 (also formed by gate structure **430C**) to storage node SN. A device-level contact **460C** electrically connects a drain region of pull-down transistor PD-2 (formed by fins **420E**, **420F** (which can include n-type epitaxial source/drain features)) and a drain region of pull-up transistor PU-2 (formed by fin **420D** (which can include p-type epitaxial source/drain

features)), such that a common drain of pull-down transistor PD-2 and pull-up transistor PU-2 form a storage node SNB. A device-level contact 460D electrically connects a gate of pull-up transistor PU-1 (formed by gate structure 430B) and a gate of pull-down transistor PD-1 (also formed by gate structure 430B) to storage node SNB. A device-level contact 460E electrically connects a source region of pull-up transistor PU-1 (formed by fin 420C (which can include p-type epitaxial source/drain features)) to a power supply voltage VDD at a voltage node VDDN1, and a device-level contact 460F electrically connects a source region of pull-up transistor PU-2 (formed by fin 420D (which can include p-type epitaxial source/drain features)) to power supply voltage VDD at a voltage node VDDN2. A device-level contact 460G electrically connects a source region of pull-down transistor PD-1 (formed by fins 420A, 420B (which can include n-type epitaxial source/drain features)) to a power supply voltage Vss at a voltage node VSSN1, and a device-level contact 460H electrically connects a source region of pull-down transistor PD-2 (formed by fins 420E, 420F (which can include n-type epitaxial source/drain features)) to power supply voltage Vss at a voltage node VSSN2. A device-level contact 460I electrically connects a source region of pass-gate transistor PG-1 (formed by fins 420A, 420B (which can include n-type epitaxial source/drain features)) to a bit line (generally referred to as a bit line node BLN), and a device-level contact 460J electrically connects a source region of pass-gate transistor PG-2 (formed by fins 420E, 420F (which can include n-type epitaxial source/drain features)) to a complementary bit line (generally referred to as a bit line node BLNB). A device-level contact 460K electrically connects a gate of pass-gate transistor PG-1 (formed by gate structure 430A) to a word line WL (generally referred to as a word line node WL), and a device-level contact 460L electrically connects a gate of pass-gate transistor PG-2 (formed by gate structure 430D) to the word line. Though not depicted, it is understood that single-port SRAM cell 400 can further include vias and/or conductive lines of a multilayer interconnect (MLI) feature electrically connected to device-level contacts 460A-460K.

[0034] FIG. 5 is a fragmentary top view of a portion of a SRAM array 500 in one embodiment of the present disclosure. In some implementations, the portion of SRAM array 500 represents a portion of memory macro 102 (FIG. 1). FIG. 5 has been simplified for the sake of clarity to better understand the inventive concepts of the present disclosure. For example, device-level contacts in a SRAM cell as described above in association with FIG. 4 are omitted. Additional features can be added in SRAM array 500, and some of the features described below can be replaced, modified, or eliminated in other embodiments of SRAM array 500.

[0035] SRAM array 500 includes a circuit region 502, n-type WPU regions 504A and 504B (collectively, as n-type WPU regions 504), and p-type WPU regions 506A and 506B (collectively as p-type WPU regions 506). Circuit region 502 includes multiple memory bit cells, such as SRAM cells 508 over n-wells and p-wells. Circuit region 502 is also referred to as memory bit cell region 502. N-type WPU regions 504 provide n-well pick-up areas to electrically couple a bias voltage to n-wells. P-type WPU regions 506 provide p-well pick-up areas to electrically couple a bias voltage to p-wells. Circuit region 502, n-type WPU regions 504, and p-type WPU regions 506, all oriented lengthwise

along an x-direction in the depicted embodiment. N-type WPU region 504A and p-type WPU region 506A are on one side of circuit region 502 with n-type WPU region 504A between circuit region 502 and p-type WPU region 506A. N-type WPU region 504B and p-type WPU region 506B are on an opposing side of circuit region 502 with n-type WPU region 504B between circuit region 502 and p-type WPU region 506B.

[0036] Circuit region 502 includes p-wells 512A, 512B, 512C, 512D (collectively, as p-wells 512) and n-wells 514A, 514B, 514C (collectively, as n-wells 514) alternately arranged along an x-direction. In other words, every p-well 512 is next to an n-well 514 which is next to another p-well 512, and this pattern repeats. An n-well 514 has a width denoted as W1, and a p-well 512 has a width denoted as W2. Generally, W1 is smaller than W2. A well boundary 516 is formed between any two oppositely doped wells. Every p-well 512 and n-well 514 further extends continuously into adjacent n-type WPU regions 504 lengthwise along an y-direction. N-wells 514 do not further extend into p-type WPU regions 506, while p-wells 512 further extend into p-type WPU regions 506. In p-type WPU regions 506, p-wells 512 expands laterally along an x-direction to connect with a neighboring p-wells. For example, p-well 512A extends with a p-well linking portion 516A to connect with p-well 512B, p-well 512B extends with a p-well linking portion 516B to connect with p-well 512C, and p-well 512C extends with a p-well linking portion 512C to connect with p-well 512D. With a p-well linking portion, a p-well 512's width expands from W2 to W3 ( $W3=W1+W2$ ) in p-type WPU regions 506. Since all p-wells 512 are connected in p-type WPU regions, they can also be regarded as portions of one single larger p-well that surrounds n-wells 514A, 514B, 514C.

[0037] Over the wells, circuit region 502 includes active regions 520 oriented lengthwise generally along an y-direction, and gate structures 522 oriented lengthwise generally along an x-direction. The active regions 520 are properly doped for forming transistors. For example, active regions 520 over p-wells 512 are doped with n-type dopants for forming n-type FETs, and active regions 520 over n-wells 516 are doped with p-type dopants for forming p-type FETs. Active regions 520 may include fins or fin active regions for FinFETs in an embodiment (similar to FinFET 300 described above with reference to FIG. 3) or may include vertically stacked multiple nanowires or nanosheets for gate-all-around (GAA) FETs in another embodiment. Active regions 520 may take other suitable forms or shapes (such as planar active regions for planar MOSFETs). Gate structures 522 may include high-k metal gate (HK/MG) structures (i.e., having one or more metal layers over a high-k gate dielectric layer) in an embodiment, and may include other materials and/or configuration in various embodiments. Gate structures 522 engage active regions 520 to form various transistors, such as n-type FinFETs, p-type FinFETs, n-type GAA FETs, and p-type GAA FETs. The transistors are properly coupled to form memory bits, such as SRAM cells. In the depicted embodiment, six SRAM cells 508 (highlighted in dotted boxes in FIG. 5) of two rows and three columns are illustrated, which is provided for illustration purposes and does not necessarily limit the embodiments of the present disclosure to any other number of rows and any other number of columns of memory bit cells. For example, the structures shown in FIG. 5 may be repeated along the

x-direction to increase number of columns of memory cells. Each of SRAM cells **508** may include a single-port SRAM, a dual-port SRAM, other type SRAM, or combinations thereof. For example, SRAM cells **508** include single-port SRAMs. In the depicted embodiment, although labeled on only one SRAM cell **508**, each of SRAM cells **508** include six transistors: a pass-gate transistor PG-1, a pass-gate transistor PG-2, a pull-up transistor PU-1, a pull-up transistor PU-2, a pull-down transistor PD-1, and a pull-down transistor PD-2 (similar to single-port SRAM cell **400** described above with reference to FIG. 4). Circuit region **502** also includes dummy areas **510** disposed between the edge of SRAM cells **508** and n-type WPU region **504**.

[0038] N-type WPU regions **504** and p-type WPU regions **506** also includes active regions **520** over the p-wells and n-wells. Active regions **520** in the WPU regions may have the same shape and configuration as active regions **520** in circuit region **502**. For example, active regions **520** over p-wells may be doped with n-type dopants, and active regions **520** over n-wells may be doped with p-type dopants. Active regions **520** are oriented lengthwise generally along an y-direction. Particularly, active regions **520** in the WPU regions are aligned with active regions **520** in circuit region **502** along the y-direction. But they are separate from each other. In some embodiments, a fin formation process first forms fins extending continuously through p-type WPU region **506A**, n-type WPU region **504A**, circuit region **502**, n-type WPU region **504B**, p-type WPU region **506B** in sequence, followed by a fin cut process that subsequently divides each fin into separated segments in each respective region. The separation is provided for effectively isolating active fin segments' functionality in circuit region **502** from interference created by other fin segments in WPU regions.

[0039] N-type WPU regions **504** and p-type WPU regions **506** further includes gate structures **522** oriented lengthwise generally along an x-direction. The gate structures **522** in the WPU regions may have the same shape and configuration as gate structures **522** in circuit regions **502**. For example, gate structures **522** may include high-k metal gate (HK/MG) structures in an embodiment and may include other materials and/or configuration in various embodiments.

[0040] N-type WPU regions **504** further includes contact features **524** disposed over and in electrical contact with n-wells **514**, and p-type WPU regions **506** further includes contact features **526** disposed over and in electrical contact with p-wells **512**. Contact features **524** and **526** are part of well pick-up structures, through which wells **512** and **514** receive voltages (or biasing) from tester equipment or other circuits. In the depicted embodiment, contact features **524** are disposed near the middle of each n-well **514** and between two active regions **520** over the respective n-well **514**, and contact features **526** are disposed near the middle of each p-well **512** and between two active regions **520** over the respective p-well **512**. There are no contact features **526** for p-well pick-up structures over either p-wells **512** in the n-type WPU region **504** or p-well linking portions **516** in p-type WPU regions **516**. Accordingly, contact features **524** and **526** are spaced out along both the x-direction (e.g., by at least 3 gate pitches) and the y-direction (e.g., by at least 3 gate pitches) for effective isolation between them. Further, the number of the contact features over each well is designed to strike a balance between providing a low well pick-up resistance and costing low. The number of contact features over each of the wells affects the resistance of the well

pick-up structure on the respective well. Having a greater number of contact features advantageously reduces the resistance of the well pick-up structure. However, it also takes up more chip areas, which means a higher cost. In some embodiments, the number of rows of the contact features **526** along an y-direction over each p-well **512** on one side of the circuit region **502** is designed to be in a range of 2 to 10 to provide low enough resistance but also be cost effective, such as 5 in the depicted embodiment. For the same reason, the number of rows of the contact features **524** along an y-direction over each n-well **514** on one side of the circuit region **502** is designed to be in a range of 2 to 10, such as 5 (e.g., equal to that of the contact features **526**) in the depicted embodiment. In each WPU region, over each n-well **514** or p-well **512**, the number of rows of the contact features **524** or contact features **526** may be less than the number of gate structures **522**, such as one less.

[0041] FIG. 6 shows a partial, cross-sectional view of SRAM array **500** in the n-type WPU region **504A** along the A-A line in FIG. 5. The device **500** includes a substrate **501**. The n-well **514B** and p-wells **512B** and **512C** are formed in and/or on the substrate **501**. Referring to FIG. 6, only half width  $W_2$  ( $W_2/2$ ) of p-wells **512B** and **512C** are shown. The active regions **520** are formed as fins over the substrate **501** in this embodiment (also referred to as fins **520**). The device **500** further includes an isolation structure **528** disposed over the substrate **501** and laterally between the fins **520**.

[0042] Substrate **501** is a silicon substrate in the depicted embodiment. Alternatively, substrate **501** may comprise another elementary semiconductor, such as germanium; a compound semiconductor including silicon carbide, gallium arsenide, gallium phosphide, indium phosphide, indium arsenide, and indium antimonide; an alloy semiconductor including silicon germanium, gallium arsenide phosphide, aluminum indium phosphide, aluminum gallium arsenide, gallium indium arsenide, gallium indium phosphide, and gallium indium arsenide phosphide; or combinations thereof.

[0043] Fins **520** may comprise the same semiconductor material(s) as substrate **501**. In an embodiment, fins **520** may include alternately stacked layers of two different semiconductor materials, such as layers of silicon and silicon germanium alternately stacked. Fins **520** may include n-type dopant(s) such as phosphorus or arsenic, or p-type dopant(s) such as boron or indium. For example, active regions **520** over p-wells may be doped with n-type dopants, and active regions **520** over n-wells may be doped with p-type dopants. Fins **520** may be patterned using one or more photolithography processes, including double-patterning or multi-patterning processes. Generally, double-patterning or multi-patterning processes combine photolithography and self-aligned processes, allowing patterns to be created that have, for example, pitches smaller than what is otherwise obtainable using a single, direct photolithography process. For example, in one embodiment, a sacrificial layer is formed over a substrate and patterned using a photolithography process. Spacers are formed alongside the patterned sacrificial layer using a self-aligned process. The sacrificial layer is then removed, and the remaining spacers, or mandrels, may then be used to pattern fins **520** by etching the initial epitaxial semiconductor layers. The etching process can include dry etching, wet etching, reactive ion etching (RIE), and/or other suitable processes. For example, a dry etching process may implement an oxygen-containing gas, a fluo-



rine-containing gas (e.g.,  $\text{CF}_4$ ,  $\text{SF}_6$ ,  $\text{CH}_2\text{F}_2$ ,  $\text{CHF}_3$ , and/or  $\text{C}_2\text{F}_6$ ), a chlorine-containing gas (e.g.,  $\text{Cl}_2$ ,  $\text{CHCl}_3$ ,  $\text{CCl}_4$ , and/or  $\text{BCl}_3$ ), a bromine-containing gas (e.g.,  $\text{HBr}$  and/or  $\text{CHBr}_3$ ), an iodine-containing gas, other suitable gases and/or plasmas, and/or combinations thereof. For example, a wet etching process may comprise etching in diluted hydrofluoric acid (DHF); potassium hydroxide (KOH) solution; ammonia; a solution containing hydrofluoric acid (HF), nitric acid ( $\text{HNO}_3$ ), and/or acetic acid ( $\text{CH}_3\text{COOH}$ ); or other suitable wet etchant.

**[0044]** Isolation structure **528** may comprise silicon oxide, silicon nitride, silicon oxynitride, fluoride-doped silicate glass (FSG), a low-k dielectric material, and/or other suitable insulating material. Isolation structure **528** may be shallow trench isolation (STI) features. Other isolation structure such as field oxide, LOCAl Oxidation of Silicon (LOCOS), and/or other suitable structures are possible. Isolation structure **528** may include a multi-layer structure, for example, having one or more thermal oxide liner layers adjacent to fins **520**.

**[0045]** Epitaxial source features and epitaxial drain features (referred to as epitaxial source/drain features) are disposed over the source/drain regions of fins **520**. For example, semiconductor material is epitaxially grown on fins **520**, forming epitaxial source/drain features **530**. In some implementations, epitaxial source/drain features **530** are formed over the source/drain regions of fins **520** after a fin recess process (for example, an etch back process), such that epitaxial source/drain features **530** are grown from recessed fins. In some implementations, epitaxial source/drain features **530** wrap the source/drain regions of fins **520**. In such implementations, fins **520** may not be subjected to a fin recess process. In the depicted embodiment, epitaxial source/drain features **530** extend (grow) laterally along the x-direction (in some implementations, substantially perpendicular to fins **520**), such that epitaxial source/drain features **530** are merged epitaxial source/drain features that span more than one fin. For example, over n-well **514B**, epitaxial source/drain feature **530** spans two fins **520**. An epitaxy process can implement CVD deposition techniques (for example, vapor-phase epitaxy (VPE), ultra-high vacuum CVD (UHV-CVD), LPCVD, and/or PECVD), molecular beam epitaxy, other suitable SEG processes, or combinations thereof. The epitaxy process can use gaseous and/or liquid precursors, which interact with the composition of substrate **501**. Epitaxial source/drain features **530** are doped with n-type dopants and/or p-type dopants. Epitaxial source/drain features **530** over p-well and n-well are oppositely doped. In the depicted embodiment, epitaxial source/drain features **530** over p-wells **512B** and **512C** are silicon germanium containing epitaxial layers doped with boron, carbon, other p-type dopant, or combinations thereof (for example, forming a Si:Ge:B epitaxial layer or a Si:Ge:C epitaxial layer). Epitaxial source/drain feature **530** over n-well **514B** is silicon-carbon-containing epitaxial layers are doped with phosphorous, arsenic, other n-type dopant, or combinations thereof (for example, forming a Si:P epitaxial layer, a Si:C epitaxial layer, or a Si:C:P epitaxial layer).

**[0046]** In some implementations, silicide layers are formed on epitaxial source/drain features **530**. In some implementations, silicide layers are formed by depositing a metal layer over epitaxial source/drain features **530**. The metal layer includes any material suitable for promoting silicide formation, such as nickel, platinum, palladium,

vanadium, titanium, cobalt, tantalum, ytterbium, zirconium, other suitable metal, or combinations thereof. A heating process, such as an annealing process is subsequently performed to cause constituents of epitaxial source/drain features **530** (for example, silicon and/or germanium) to react with the metal. Silicide layers thus include metal and a constituent of epitaxial source/drain features **530** (for example, silicon and/or germanium). In some implementations, silicide layers include nickel silicide, titanium silicide, or cobalt silicide. Any un-reacted metal, such as remaining portions of the metal layer, is selectively removed by any suitable process, such as an etching process. In some implementations, the silicide layers and epitaxial source/drain features **530** are collectively referred to as the epitaxial source/drain features.

**[0047]** A multilayer interconnect (MLI) feature **532** is disposed over substrate **501**. MLI feature **532** electrically couples various devices (for example, transistors, resistors, capacitors, and/or inductors) and/or components (for example, gate structures and/or source/drain features), such that the various devices and/or components can operate as specified by design requirements of SRAM array **500**. MLI feature **532** includes a combination of dielectric layers and electrically conductive layers (for example, metal layers) configured to form various interconnect structures. The conductive layers are configured to form vertical interconnect features, such as device-level contacts and/or vias, and/or horizontal interconnect features, such as conductive lines. Vertical interconnect features typically connect horizontal interconnect features in different layers (or different planes) of MLI feature **532**. It is noted that though MLI feature **532** is depicted with a given number of dielectric layers and conductive layers, the present disclosure contemplates MLI feature **532** having more or less dielectric layers and/or conductive layers.

**[0048]** MLI feature **532** includes one or more dielectric layers, such as an interlayer dielectric layer **534** (ILD-0) disposed over substrate **501**, an interlayer dielectric layer **536** (ILD-1) disposed over ILD layer **534**, and an interlayer dielectric layer **538** (ILD-2) disposed over ILD layer **536**. ILD layers **534**, **536**, and **538** include a dielectric material including, for example, silicon oxide, silicon nitride, silicon oxynitride, TEOS formed oxide, PSG, BPSG, low-k dielectric material, other suitable dielectric material, or combinations thereof. Exemplary low-k dielectric materials include FSG, carbon doped silicon oxide, Black Diamond® (Applied Materials of Santa Clara, California), Xerogel, Aerogel, amorphous fluorinated carbon, Parylene, BCB, SILK® (Dow Chemical, Midland, Michigan), polyimide, other low-k dielectric material, or combinations thereof. In the depicted embodiment, ILD layers **534**, **536**, and **538** are dielectric layers that include a low-k dielectric material (generally referred to as low-k dielectric layers). In some implementations, low-k dielectric material generally refers to materials having a dielectric constant (k) that is less than 3. ILD layers **534**, **536**, and **538** can include a multilayer structure having multiple dielectric materials. ILD layers **534**, **536**, and **538** are formed over substrate **501** by a deposition process, such as CVD, PVD, ALD, HDPCVD, MOCVD, RPCVD, PECVD, LPCVD, ALCVD, APCVD, plating, other suitable methods, or combinations thereof. In some implementations, ILD layers **534**, **536**, and **538** are formed by a flowable CVD (FCVD) process that includes, for example, depositing a flowable material (such as a liquid

compound) over substrate **501** and converting the flowable material to a solid material by a suitable technique, such as thermal annealing and/or ultraviolet radiation treating. Subsequent to the deposition of ILD layers **534**, **536**, and **538**, a CMP process and/or other planarization process is performed, such that ILD layers **534**, **536**, and **538** have substantially planar surfaces.

[0049] A contact **524** and a conductive line **540** (such as metal 1) are disposed in ILD layers **536** and **538** to form interconnect structures. In some implementations, MLI feature **532** further includes vias interposed between contact **524** and conductive line **540**. Contact **524** and conductive line **540** include any suitable electrically conductive material, such as Ta, Ti, Al, Cu, Co, W, TiN, TaN, other suitable conductive materials, or combinations thereof. In some implementations, contact **524** include Ti, TiN, and/or Co and conductive line **540** include Cu, Co, and/or Ru. Contact **524** electrically couples n-well **514B** to conductive line **540**, which in turn connects to bias voltages (such as Vdd or Vss depicted in FIG. 2). As discussed above, contact features for p-well pick-up structures are all in p-type WPU regions **506**, there are no contacts over either p-wells **512B** or **512C** in the n-type WPU regions **504**.

[0050] Still referring to FIG. 6, in substrate **501**, n-well **514B** is next to p-well **512B** and p-well **512C**. Well boundaries **516** as an interface between a pair of two oppositely doped wells are indicated with dashed lines. In a proximity region around each well boundary **516**, dopants in two oppositely doped wells diffuse into each other, forming a diffusion area **530** indicated with a dotted box. Inside diffusion area **530**, opposite dopants from n-well and p-well neutralize, resulting in a high resistant area along well boundary **516**. A width of diffusion area **530** is denoted as W4. Diffusion area **530** reduces equivalent width of n-well **514B** from W1 down to W1-W4. Similarly, diffusion area **530** reduces equivalent width of p-well **512B** or p-well **512C** from W2 down to W2-W4. In some embodiments, W1-W4 is about half of W1. With reduced equivalent well width, resistances at bottom of n-well and p-well both increase. Since in SRAM array **500**, n-wells are generally narrower than p-wells, equivalent width reduction has more impact on n-wells than p-wells. Further, since p-well pick-up structures are in p-type WPU region **506** that is free of diffusion areas, reduction of well equivalent width in n-type WPU regions **504** does not impact p-well pick-up structures' resistance as much as n-well pick-up structures. In some cases, n-well pick-up structure's resistance may be increased one or two orders higher with the existence of diffusion area **530**. In a specific example, the existence of diffusion area **530** may significantly increase n-well pick-up structure's resistance, such as about 10 times larger. Higher n-well pick-up structure's resistance also triggers latch-up more easily. To mitigate n-well equivalent width reduction, one option is to increase n-well width in n-type WPU regions **504**, which is discussed in further details below.

[0051] FIG. 7 is a fragmentary top view of a portion of SRAM array **500** in another embodiment of the present disclosure. Reference numerals in FIGS. 5 and 7 are repeated for ease of understanding. Many aspects of SRAM cell **500** are the same as to what have been discussed above with reference to FIG. 5 and omitted here for the sake of convenience. One difference of SRAM array **500** in FIG. 7 compared with FIG. 5 is that width of an n-well **514** in n-type WPU region **504** expands from W1 to W1'. In some

implementations, W1' is two or three fin pitches (denoted as FP) wider than W1. For example, n-well **516** may expand one fin pitch on each side of n-well **516** to expand a width by two fin pitches ( $W1'=W1+2FP$ ) in total, while the width of n-well **516** in circuit region **502** remains W1. In the illustrated embodiment, by extending one fin pitch on each side, n-well **516** extends to beneath an adjacent active region **520** that would otherwise be above p-well **512**. While along this active region **520**'s lengthwise extension (along a y-direction) into circuit region **502**, the other active region **520** remains over p-well **512**.

[0052] Well boundary **516** is split into two segments **516A** and **516B** which are no longer aligned along a y-direction but generally parallel and spaced apart along an x-direction. Segment **516A** of well boundary is between n-well **514** and p-well **512** in circuit region **502**, and segment **516B** of well boundary is between n-well **514** and p-well **512** in n-type WPU regions **504**, which is offset by  $(W1'-W1)/2$  along an x-direction. Enlarging width of n-well **514** in n-type WPU regions **504** by W1'-W1 effectively increases n-well width, which mitigates equivalent width reduction due to diffusion areas **530** (FIG. 6) between oppositely doped wells. In some embodiments, n-type pick-up structures' resistance is reduced about one or two orders compared with n-well with a uniform width. In a specific example, by enlarging n-well width in n-type WPU regions **504**, n-type pick-up structures' resistance is reduced down to less than about 5% compared with n-type pick-up structures without enlarging n-well width, such as about 1%.

[0053] Enlarging (or expanding) width of n-wells **514** reduces width of p-well **512** in n-type WPU regions **504** from W2 down to W2'. In some implementations, W2' is two or three fin pitches narrower than W2. A p-well **512**'s expanded width W3 in p-type WPU regions **506** remains the same and roughly has a relationship of  $W3=W1'+W2'$  (i.e.,  $W3>W1'$ ). Since in n-type WPU regions **504**, p-wells are generally wider than n-wells, and further since p-well pick-up structures are in p-type WPU region **506** instead of in n-type WPU region **504**, the p-well width reduction in n-type WPU region **504** relatively has small impact on p-well pick-up structure's resistance. Overall, expanding width of n-well **514** in n-type WPU regions **504** significantly reduces n-well pick-up structure's resistance without sacrificing p-well pick-up structure's resistance.

[0054] Enlarging (or expanding) width of n-wells **514** in n-type WPU regions **504** also advantageously allows reducing number of rows of contact features **524**, which in turn saves more chip areas. FIG. 8 is a fragmentary top view of a portion of SRAM array **500** in yet another embodiment of the present disclosure. Reference numerals in FIGS. 7 and 8 are repeated for ease of understanding. Many aspects of SRAM cell **500** are the same as to what have been discussed above with reference to FIG. 7 and omitted here for the sake of convenience. One difference of SRAM array **500** in FIG. 8 compared with FIG. 7 is that height (H) of n-type WPU region **504** is reduced, such as by two gate pitches (GP) in the depicted embodiment. Accordingly, number of rows of contact features **524** is also reduced. In the depicted embodiment, number of rows of contact features **524** in n-type WPU region **504** is less than that of contact features **526** in p-type WPU region **506** by two. Having a less number of contact features generally increases the resistance of the well pick-up structure. However, in the embodiment illustrated in FIG. 8, a less number of contact features is compensated by

resistance reduction introduced by a wider n-well in n-type WPU regions **504**. Overall, resistance of the n-type well pick-up structure may maintain at the same level or even less. Without sacrificing the resistance of the n-type well pick-up structure, layout areas can be saved by reducing height of n-type WPU region **504**. In some embodiments, by reducing height of n-type WPU region **504** alone could save about 10% to about 15% (e.g., 13%) area from SRAM array **500**.

[0055] FIG. 9 is a fragmentary top view of a portion of SRAM array **500** in yet another embodiment of the present disclosure. Reference numerals in FIGS. 7 and 9 are repeated for ease of understanding. Many aspects of SRAM cell **500** are the same as to what have been discussed above with reference to FIG. 7 and omitted here for the sake of convenience. Similar as the embodiment depicted in FIG. 7, width of n-well **514** is enlarged in n-type WPU region **504** to reduce n-well resistance. One difference is that in the embodiment depicted in FIG. 9, in each of n-type WPU regions **504A** and **504B**, n-well **514** expands laterally along an x-direction to connect with a neighboring n-well **514**. For example, in n-type WPU region **504A**, n-well **514B** expands an n-well linking portion **515B** from an edge facing n-well **514C** and connects with n-well **514C**. The other edge of n-well **514B** facing n-well **514A** remains unchanged in n-type WPU region **504A**. Yet, in n-type WPU region **504B**, n-well **514B** expands an n-well linking portion **515A** from the other edge facing n-well **514A** and connects with n-well **514A**. The edge facing n-well **514C** remains unchanged in n-type WPU region **504B**. In this way, since all n-wells **514** are connected, they can also be regarded as one single larger n-well with an “serpentine” shape (or an “S” shape as depicted in FIG. 9). In the depicted embodiment, only three n-wells **514** are illustrated with n-wells **514A** and **514C** disposed near two edge of SRAM array **500**. If in other embodiments, there are other n-wells disposed along an x-direction outside of n-wells **514A** and **514C**, similarly, n-well **514A** will extend an n-well linking portion in n-type WPU region **504A** outwardly to connect with another neighboring n-well, and n-well **514C** will extend an n-well linking portion in n-type WPU region **504B** outwardly to connect with yet another neighboring n-well. By connecting all n-wells **514** together, n-wells **514** have an expanded width in the n-type WPU region **504**, also the number of diffusion regions **530** (FIG. 6) in each N-type WPU region **504** is reduced by half, which jointly help reducing resistance of n-well pick-up structures.

[0056] Still referring to FIG. 9, n-well linking portion **515A** separates p-well **512B** from connecting to p-type WPU region **506B**, and n-well linking portion **515B** separates p-well **512C** from connecting to p-type WPU region **506A**. Since all p-wells are still connected as portions of one single larger p-well, which effectively lowers the resistance of p-well pick-up structures, a balance between resistances of p-well pick-up structures and n-well pick-up structures are able to achieve. Further, although in the depicted embodiment, number of rows of contact features **524** in each n-type WPU region **504** equals to number of rows of contact features **526** in each p-type WPU region **506**, number of rows of contact features **524** can be reduced (e.g., n-type WPU region **504** can be reduced in height (H)) to save production cost and to save layout area. For example, number of rows of contact features **524** may be reduced by

two, and n-type WPU region **504** may be reduced in height (H) by two gate pitches (GP) in some embodiments.

[0057] Although not intended to be limiting, one or more embodiments of the present disclosure provide many benefits to a semiconductor device and the formation thereof. For example, embodiments of the present disclosure provide reduced n-well pick-up resistance in well pick-up (WPU) regions of a memory macro, by mitigating impacts from diffusion areas along well boundaries between adjacent oppositely doped wells. Further, reduction of n-well pick-up resistance does not sacrifice p-well pick-up resistance, with a balance of n-well and p-well pick-up resistances achieved. Further, embodiments of the present disclosure can be readily integrated into existing semiconductor manufacturing processes.

[0058] In one exemplary aspect, the present disclosure is directed to a semiconductor device. The semiconductor device includes a circuit region; a first well pick-up (WPU) region; a first well oriented lengthwise along a first direction in the circuit region and extending into the first WPU region, the first well having a first conductivity type; and a second well oriented lengthwise along the first direction in the circuit region and extending into the first WPU region, the second well having a second conductivity type different from the first conductivity type, wherein: the first well has a first portion in the circuit region and a second portion in the first WPU region, the first portion of the first well and the second well form a first well boundary, the second portion of the first well and the second well form a second well boundary, and the second portion of the first well has a width larger than the first portion of the first well along a second direction perpendicular to the first direction. In some embodiments, the semiconductor device further includes a second WPU region, wherein: the first WPU region is disposed between the circuit region and the second WPU region, the second well extends further into the second WPU region, and the second well has a portion in the second WPU region with a width larger than other portions of the second well in either the circuit region or the first WPU region along the second direction. In some embodiments, the width of the portion of the second well in the second WPU region is larger than the width of the second portion of the first well in the first WPU region along the second direction. In some embodiments, the semiconductor device further includes first contact features disposed over the first well in the first WPU region and arranged in a first number of rows along the first direction; and second contact features disposed over the second well in the second WPU region and arranged in a second number of rows along the first direction. In some embodiments, the first number of rows equals the second number of rows. In some embodiments, the first number of rows is less than the second number of rows. In some embodiments, the first well boundary and the second well boundary are aligned along the first direction. In some embodiments, the first well boundary and the second well boundary are generally parallel and spaced along the second direction. In some embodiments, the first well further includes a third portion in the circuit region, the third portion is generally parallel with the first portion of the first well, and the third portion connects with the second portion of the first well. In some embodiments, the semiconductor device further includes a first active region extending lengthwise along the first direction over the first well in the WPU region; and a second active region extending lengthwise

along the first direction over the second well in the circuit region, wherein first and second active regions are lengthwise generally aligned along the first direction. In some embodiments, the first and second active regions are discontinued at a boundary between the circuit region and the first WPU region. In some embodiments, the first well is an n-type well and the second well is a p-type well.

**[0059]** In another exemplary aspect, the present disclosure is directed to a memory macro. The memory macro includes a memory bit cell region; a first well pick-up (WPU) region on a first side of the memory bit cell region; a second WPU region on the first side of the memory bit cell region, wherein the memory bit cell region, the first WPU region, and second WPU region are arranged along a first direction in sequence; and n-type wells and p-type wells arranged alternately in the memory bit cell region along a second direction perpendicular to the first direction, wherein the n-type wells extend along the first direction into the first WPU region, wherein at least one of the p-type wells extends along the first direction across the first WPU region and into the second WPU region,

**[0060]** wherein at least one of the n-type wells has a portion in the first WPU region with a width larger than another portion in the memory bit cell region along the second direction. In some embodiments, the n-type wells and p-type wells are also arranged alternately in the first WPU region along the second direction, such that the at least one of the n-type wells is separated from the adjacent n-type wells by the p-type wells. In some embodiments, the at least one of the n-type wells connects with one of the adjacent n-type wells in the first WPU region. In some embodiments, the memory macro further includes a third WPU region on a second side of the memory bit cell region, the second side opposing the first side, the n-type wells extending along the first direction into the third WPU region, wherein the at least one of the n-type wells connects with the other one of the adjacent n-type wells in the third WPU region. In some embodiments, wherein the second WPU region is free of the n-type wells.

**[0061]** In yet another exemplary aspect, the present disclosure is directed to a layout of a static random access memory (SRAM) array. The layout includes a memory bit cell area; a well pick-up (WPU) area adjacent to the memory bit cell area; a n-type well and a p-type well each oriented lengthwise along a first direction in the memory bit cell area and the WPU area, the n-type and p-type wells having a well boundary therebetween; a first fin oriented lengthwise along the first direction in the memory bit cell area and the WPU area, the first fin including a first segment over the n-type well and a second segment over the p-type well, the second segment being disconnected from the first segment; and

**[0062]** gate structures over the first fin in the memory bit cell area and oriented lengthwise along a second direction perpendicular to the first direction. In some embodiments, the layout further includes first contact features disposed over the n-type well; and second contact features disposed over the p-type well, wherein a number of rows of the first contact features along the first direction is less than the second contact features. In some embodiments, the layout further includes a second fin adjacent to the first fin, wherein the second fin

extends lengthwise along the first direction over the p-type well in both the memory bit cell area and the WPU area.

**[0063]** The foregoing outlines features of several embodiments so that those skilled in the art may better understand the aspects of the present disclosure. Those skilled in the art should appreciate that they may readily use the present disclosure as a basis for designing or modifying other processes and structures for carrying out the same purposes and/or achieving the same advantages of the embodiments introduced herein. Those skilled in the art should also realize that such equivalent constructions do not depart from the spirit and scope of the present disclosure, and that they may make various changes, substitutions, and alterations herein without departing from the spirit and scope of the present disclosure.

What is claimed is:

1. A semiconductor device, comprising:
  - a circuit region;
  - a first well pick-up (WPU) region;
  - a first well oriented lengthwise along a first direction in the circuit region and extending into the first WPU region, the first well having a first conductivity type; and
  - a second well oriented lengthwise along the first direction in the circuit region and extending into the first WPU region, the second well having a second conductivity type different from the first conductivity type,
 wherein:
  - in the circuit region, the first well interfaces the second well to form a first well boundary extending along the first direction, and
  - measured along a second direction perpendicular to the first direction, the first well has a larger width in the first WPU region than in the circuit region.
2. The semiconductor device of claim 1, wherein, measured along the second direction, the second well has a larger width in the circuit region than in the first WPU region.
3. The semiconductor device of claim 1, wherein the first well is an n-type well, and the second well is a p-type well.
4. The semiconductor device of claim 1, wherein:
  - in the first WPU region, the first well interfaces the second well to form a second well boundary extending along the first direction, and
  - the second well boundary is offset from the first well boundary along the second direction.
5. The semiconductor device of claim 1, wherein the first well is fully surrounded by the second well in a top view of the semiconductor device.
6. The semiconductor device of claim 1, further comprising:
  - a second WPU region,
 wherein:
  - along the first direction, the first WPU region is disposed between the circuit region and the second WPU region, and
  - the second well extends further into the second WPU region.
7. The semiconductor device of claim 6, wherein, measured along the second direction, the second well has a larger width in the second WPU region than in the first WPU region.
8. The semiconductor device of claim 6, further comprising:

first contact features disposed over the first well in the first WPU region and arranged in a first number of rows along the first direction; and  
 second contact features disposed over the second well in the second WPU region and arranged in a second number of rows along the first direction.

9. The semiconductor device of claim 8, wherein the first number of rows equals the second number of rows.

10. The semiconductor device of claim 8, wherein the first number of rows is less than the second number of rows.

11. A memory device, comprising:  
 a cell region including an array of memory cells;  
 a first well pick-up (WPU) region disposed on a first side of the cell region;  
 a second WPU region disposed on the first side of the cell region, wherein the cell region, the first WPU region, and second WPU region are arranged along a first direction in sequence; and

n-type wells and p-type wells arranged alternately in the cell region along a second direction perpendicular to the first direction, wherein the n-type wells extend along the first direction into the first WPU region but not into the second WPU region, wherein the p-type wells extend along the first direction into the first WPU region and the second WPU region.

12. The memory device of claim 11, wherein at least one of the n-type wells has a first width in the first WPU region measured along the second direction and a second width in the cell region measured along the second direction, and wherein the first width is larger than the second width.

13. The memory device of claim 11, wherein at least one of the p-type wells has a first width in the first WPU region measured along the second direction and a second width in the cell region measured along the second direction, and wherein the first width is smaller than the second width.

14. The memory device of claim 13, wherein the n-type wells and p-type wells are also arranged alternately in the first WPU region along the second direction.

15. The memory device of claim 11, further comprising:  
 a third WPU region disposed on a second side of the cell region, the second side opposing the first side,

wherein the n-type wells and p-type wells extend along the first direction into the third WPU region.

16. The memory device of claim 15, further comprising:  
 a fourth WPU region disposed on the second side of the cell region, wherein the fourth WPU region, the third WPU region, and cell region are arranged along the first direction in sequence,

wherein the p-type wells extend along the first direction into the fourth WPU region, and the fourth WPU region is free of the n-type wells.

17. A semiconductor device, comprising:

a circuit region;  
 a well pick-up (WPU) area adjacent to the circuit region;  
 a n-type well and a p-type well each oriented lengthwise along a first direction in the circuit region and the WPU area, the n-type and p-type wells having a well boundary therebetween;

an active region oriented lengthwise along the first direction in the circuit region and the WPU area, the active region having a first segment in the WPU area and over the n-type well and a second segment in the circuit region and over the p-type well, the second segment disconnected from the first segment;

a first gate structure across the first segment in the WPU area; and

a second gate structure across the second segment in the circuit region.

18. The semiconductor device of claim 17, wherein the n-type well has a first width in the WPU area and a second width in the circuit region, the first width is larger than the second width, the p-type well has a third width in the WPU area and a fourth width in the circuit region, and wherein the third width is smaller than the fourth width.

19. The semiconductor device of claim 17, wherein, measured along the first direction, the second segment is longer than the first segment.

20. The semiconductor device of claim 17, wherein, measured along the first direction, the first segment is longer than the second segment.

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